

METHOD FOR PRODUCING PELLICLE, AND  
METHOD FOR PRODUCING PELLICLE-ATTACHED PHOTOMASK

**ABSTRACT**

Foreign object particles generated at the time of trimming is suppressed from being attached to a pellicle film. A method for  
5 producing a pellicle according to the present invention produces a pellicle including a pellicle film and a pellicle frame supporting an outer peripheral portion of the pellicle film. The method includes forming the pellicle film on a substrate, and bonding a pressure-sensitive adhesive sheet, that is elastic and has a pressure-sensitive adhesive force thereof  
10 decreased upon receipt of external stimulation, to each of two surfaces of the substrate; making a notch inside a part of the substrate, the part having the pressure-sensitive adhesive sheets bonded thereto; separating a substrate outer peripheral portion outer to the notch of the substrate, in a state where the pressure-sensitive adhesive sheets are  
15 bonded to the substrate, to form a pellicle frame; and stimulating the pressure-sensitive adhesive sheets to peel off the pressure-sensitive adhesive sheets.

Figure 4C

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